

L Number	Hits	Search Text	DB	Time stamp
-	121	partial adj pressure same control\$4 and 117/\$4.ccls. and (si or silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/30 15:00
-	18	partial adj pressure same control\$4 and 117/\$4.ccls. and (si or silicon) same melt	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/30 15:03
-	13	partial adj pressure same control\$4 and (117/11-83.ccls. or 117/200-224.ccls.) and (si or silicon) same melt	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/30 15:37
-	20	maragoni	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/30 15:31
-	118	(oxygen or o2 or "o.sub.2") near3 (pressure or concentration) same control\$3 and (117/11-83.ccls. or 117/200-224.ccls.) and (si or silicon) same melt	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/30 16:04
-	66	(oxygen or o2 or "o.sub.2") near3 (pressure or concentration) same control\$3 and (117/11-83.ccls. or 117/200-224.ccls.) and (si or silicon) same melt and atmosphere	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/30 16:04
-	15	(oxygen or o2 or "o.sub.2") near3 (pressure or concentration) same control\$3 same atmosphere and (117/11-83.ccls. or 117/200-224.ccls.) and (si or silicon) same melt	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 10:55
-	115	(oxygen or o2 or "o.sub.2") near3 (pressure or concentration) and (117/11-83.ccls. or 117/200-224.ccls.) and (si or silicon) same melt and (ar or argon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 11:00
-	17	(oxygen or o2 or "o.sub.2") near3 (pressure) and (117/11-83.ccls. or 117/200-224.ccls.) and (si or silicon) same melt and (ar or argon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 11:35
-	5	(oxygen or o2 or "o.sub.2") near3 (pressure) same rad\$4 and (si or silicon) same melt	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 11:37
-	3	(oxygen or o2 or "o.sub.2") near3 (pressure) same (radial or radius or radia or radial\$2 or radii) and (si or silicon) same melt	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 11:39
-	93	(oxygen or o2 or "o.sub.2") near3 (pressure) same gradient and (silicon or si)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 11:41
-	3	(oxygen or o2 or "o.sub.2") near3 (pressure) same gradient and (silicon or si) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 11:43

-	12	(oxygen or o2 or "o.sub.2") near3 (pressure) same gradient and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 11:43
-	32	(oxygen or o2 or "o.sub.2") near3 (pressure) and (si or silicon) same melt and float	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 11:52
-	7	(oxygen or o2 or "o.sub.2") near3 (pressure) and (si or silicon) same melt and (float near2 zone or fz)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 13:13
-	10	(oxygen or o2 or "o.sub.2") near3 (pressure) and (si or silicon) same melt and (floating near2 zone)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 13:15
-	27	(buoyan\$4 or bouyan\$4) same convect\$3 and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 17:07
-	17	marangoni and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 16:53
-	4	(buoyan\$4 or bouyan\$4) same convect\$3 and 117/\$4.ccls. and marangoni	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 17:12
-	79	117/\$4.ccls. and (fz or float\$3 near3 zone) and (oxygen or o2 or "o.sub.2") same (pressure or concentration)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/03 17:14
-	24	117/\$4.ccls. and (fz or float\$3 near3 zone) and (oxygen or o2 or "o.sub.2") near10 (pressure)	USPAT; US-PGPUB; EPO; DERWENT; IBM_TDB	2002/09/03 17:16
-	7	117/\$4.ccls. and (fz or float\$3 near3 zone) and (oxygen or o2 or "o.sub.2") near10 (pressure) and (silicon or si)	USPAT; US-PGPUB; EPO; DERWENT; IBM_TDB	2002/09/03 17:16
-	67	(oxygen or o2 or "o.sub.2") same partial same pressure same control\$4 and (si or silicon) same melt	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/04 11:53
-	10	((oxygen or o2 or "o.sub.2") same partial same pressure same control\$4 and (si or silicon) same melt) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/04 15:18
-	21	((oxygen or o2 or "o.sub.2") same partial same pressure and (si or silicon) same melt) and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/04 15:40
-	43	(oxygen or o2 or "o.sub.2") same partial same pressure and czochralski and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/04 15:41

-	26	(oxygen or o2 or "o.sub.2") same partial same pressure and czochralski and 117/\$4.ccls. and (silicon or si)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/04 15:43
-	34	(oxygen or o2 or "o.sub.2") near5 pressure and (silicon or si) same melt and 117/\$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/04 16:56
-	5	drift adj convection	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/04 16:57